

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	22884	(resist or photoresist) same (ash\$6 or remov\$6 or incinerat\$6) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L2	397315	(dielectric or SiC or silicate or IMD or IML or IDM or IDL or glass or hole or viahole or contacthole) same (pattern\$6 or etch\$6 or mask\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L3	12184	L1 and L2 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L4	10766	L3 and (@ad<="20021129" or @rlad<="20021129")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 17:55
L15	18179	(HF or hydrofluoric or (hydro adj fluoric) or (fluoric adj acid)) same (salt or NH4F or ammonium or (NH?sub\$3 adj F))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 18:16
L20	591	4 and 15	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 18:16

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L2	397315	(dielectric or SiC or silicate or IMD or IML or IDM or IDL or glass or hole or viahole or contacthole) same (pattern\$6 or etch\$6 or mask\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L3	12184	L1 and L2 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L4	10766	L3 and (@ad<="20021129" or @rlad<="20021129")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L5	2035	L1 same (degree or celcius or temperature) same (time or second or sec or minute or min)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L6	1190	L4 and L5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L7	975	L6 and (nitrogen or N2 or hydrogen or H2 or N?sub\$3 or H?sub\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:50
L8	442	7 and (HF or hydrofluoric or (hydro adj fluoric) or (fluoric adj acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 16:52